



<b>FORM PTO - 1449</b>				<b>ATTY DOCKET NO.:</b> ASC-023DVC2					
<b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT</b>				<b>APPLICANT:</b> Fitzgerald					
				<b>SERIAL NO.:</b> 10/022,689					
				<b>FILING DATE:</b> December 17, 2001					
				<b>GROUP:</b> 2813					
<b>U.S. PATENT DOCUMENTS</b>									
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE		
<i>HL</i>	A117	5,424,243	06/13/1995	Takasaki					
	A118	2002/0052084	05/02/2002	Fitzgerald			05/16/2001		
<i>J</i>	A119	2003/0077867	04/24/2003	Fitzgerald			07/16/2001		
<i>HL</i>	A120	6,602,613	08/05/2003	Fitzgerald			01/17/2001		
<b>FOREIGN PATENT DOCUMENTS</b>									
EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
<b>OTHER ART, JOURNAL ARTICLES, ETC.</b>									
EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)								
<b>EXAMINER</b>		<i>Wesley Schelf</i>			<b>DATE CONSIDERED</b> 3/13/07				

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SUPPLEMENTAL INFORMATION  
DISCLOSURE STATEMENT

ATTY DOCKET NO.: ASC-023DVC2

APPLICANTS: Fitzgerald

SERIAL NO.: 10/022,689

FILING DATE: December 17, 2001

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## U.S. PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>sh</i>	A1	4,010,045	03/01/1977	Ruehrwein			
	A2	4,710,788	12/01/1987	Dambkes et al.			
	A3	4,987,462	01/22/1991	Kim et al.			
	A4	4,990,979	02/05/1991	Otto			
	A5	5,013,681	05/07/1991	Godbey et al.			
	A6	5,155,571	10/13/1992	Wang et al.			
	A7	5,166,084	11/24/1992	Pfiester			
	A8	5,202,284	04/01/1993	Kamins et al.			
	A9	5,207,864	05/04/1993	Bhat et al.			
	A10	5,208,182	05/04/1993	Narayan et al.			
	A11	5,212,110	05/18/1993	Pfiester et al.			
	A12	5,221,413	06/22/1993	Brasen et al.			
	A13	5,241,197	08/31/1993	Murakami et al.			
	A14	5,285,086	02/08/1994	Fitzgerald, Jr.			
	A15	5,291,439	03/01/1994	Kauffmann, et al.			
	A16	5,310,451	05/10/1994	Tejwani et al.			
	A17	5,316,958	05/31/1994	Meyerson			
	A18	5,346,848	09/13/1994	Gruppen-Shemansky et al.			
	A19	5,374,564	12/20/1994	Bruel			
	A20	5,413,679	05/09/1995	Godbey			
	A21	5,426,069	06/20/1995	Selvakumar et al.			
	A22	5,426,316	06/20/1995	Mohammad			
	A23	5,461,243	10/24/1995	Ek et al.			
	A24	5,461,250	10/24/1995	Burghartz et al.			
	A25	5,462,883	10/31/1995	Dennard et al.			
	A26	5,476,813	12/19/1995	Naruse			
	A27	5,479,033	12/26/1995	Baca et al.			
	A28	5,484,664	01/16/1996	Kitahara et al.			
	A29	5,523,243	06/04/1996	Mohammad			
<i>sh</i>	A30	5,523,592	06/04/1996	Nakagawa et al.			

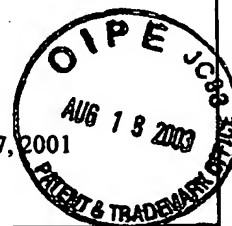
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DATE CONSIDERED

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<b>FORM PTO - 1449</b>  <b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT</b>	ATTY DOCKET NO.:	ASC-023DVC2
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## U.S. PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
JK	A31	5,536,361	07/16/1996	Kondo et al.			
	A32	5,540,785	07/30/1996	Dennard et al.			
	A33	5,596,527	01/12/1997	Tomiooka, et al.			
	A34	5,617,351	04/01/1997	Bertin, et al.			
	A35	5,683,934	11/04/1997	Candelaria			
	A36	5,698,869	12/16/1997	Yoshimi et al.			
	A37	5,728,623	03/17/1998	Mori			
	A38	5,739,567	04/14/1998	Wong			
	A39	5,759,898	06/02/1998	Ek et al.			
	A40	5,777,347	07/07/1998	Bartelink			
	A41	5,786,612	07/28/1998	Otani et al.			
	A42	5,786,614	07/28/1998	Chuang, et al.			
	A43	5,792,679	08/11/1998	Nakato			
	A44	5,808,344	09/15/1998	Ismail et al.			
	A45	5,847,419	12/08/1998	Imai et al.			
	A46	5,877,070	03/02/1999	Goesle et al.			
	A47	5,906,708	05/25/1999	Robinson et al.			
	A48	5,912,479	06/15/1999	Mori et al.			
	A49	5,943,560	08/24/1999	Chang et al.			
	A50	5,963,817	10/05/1999	Chu et al.			
	A51	5,966,622	10/12/1999	Levine et al.			
	A52	5,998,807	12/07/1999	Lustig et al.			
	A53	6,013,134	01/11/2000	Chu et al.			
	A54	6,033,974	03/07/2000	Henley et al.			
	A55	6,033,995	03/07/2000	Muller			
	A56	6,058,044	05/02/2000	Sugiura et al.			
	A57	6,074,919	06/13/2000	Gardner et al.			
	A58	6,096,590	08/01/2000	Chan et al.			
	A59	6,103,559	08/15/2000	Gardner et al.			
JK	A60	6,111,267	08/29/2000	Fischer et al.			


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U.S. PATENT DOCUMENTS							
EXAM. INIT.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
JLH	A61	6,117,750	09/12/2000	Bensahel et al.			
	A62	6,130,453	10/10/2000	Mei, et al.			
	A63	6,133,799	10/17/2000	Favors, Jr., et al.			
	A64	6,140,687	10/31/2000	Shimomura et al.			
	A65	6,143,636	11/07/2000	Forbes, et al.			
	A66	6,153,495	11/28/2000	Kub et al.			
	A67	6,154,475	11/28/2000	Soref et al.			
	A68	6,160,303	12/12/2000	Fattarusio			
	A69	6,162,688	12/19/2000	Gardner et al.			
	A70	6,184,111	02/06/2001	Henley et al.			
	A71	6,191,007	02/20/2001	Matsui et al.			
	A72	6,191,432	02/20/2001	Sugiyama et al.			
	A73	6,194,722	02/27/2001	Fiorini et al.			
	A74	6,204,529	03/20/2001	Lung, et al.			
	A75	6,207,977	03/01/2001	Augusto			
	A76	6,210,988	04/03/2001	Howe et al.			
	A77	6,218,677	04/17/2001	Brockaert			
	A78	6,232,138	05/15/2001	Fitzgerald et al.			
	A79	6,235,567	05/22/2001	Huang			
	A80	6,242,324	06/05/2001	Kub et al.			
	A81	6,249,022	06/19/2001	Lin, et al.			
	A82	6,251,755	06/26/2001	Furukawa et al.			
	A83	6,261,929	07/01/2001	Gehrke et al.			
	A84	6,266,278	07/24/2001	Harari, et al.			
	A85	6,271,551	08/07/2001	Schmitz et al.			
	A86	6,271,726	08/07/2001	Fransis et al.			
	A87	6,313,016	11/06/2001	Kibbel et al.			
	A88	6,316,301	11/13/2001	Kant			
JLH	A89	6,323,108	11/27/2001	Kub et al.			
	A90	6,329,063	12/11/2001	Lo et al.			

<b>EXAMINER</b> <i>Norma Schulz</i>	<b>DATE CONSIDERED</b> <i>8/4/04</i>
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## U.S. PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>HL</i>	A91	6,335,546	01/01/2002	Tsuda et al.			07/30/1999
	A92	6,339,232	01/15/2002	Takagi			09/20/1999
	A93	6,368,733	04/09/2002	Nishinaga			08/05/1999
	A94	6,372,356	04/16/2002	Thornton et al.			04/028/2000
	A95	6,399,970	06/04/2002	Kubo et al.			09/16/1997
	A96	6,407,406	06/18/2002	Tezuka			06/29/1999
	A97	6,425,951	07/30/2002	Chu et al.			08/06/1999
	A98	6,429,061	08/06/2002	Rim			07/26/2000
	A99	6,420,937	07/16/2002	Akatsuka et al.			06/14/2001
	A100	6,521,041	02/18/2003	Wu et al.			04/09/1999
	A101	6,555,839	04/29/2003	Fitzgerald			05/16/2001
	A102	6,583,015	06/24/2003	Fitzgerald et al.			08/06/2001
	A103	6,521,041	02/18/2003	Wu et al.			04/09/1999
	A104	2001/0003364	06/14/2001	Sugawara et al.			12/08/2000
	A105	2002/0043660	04/18/2002	Yamazaki et al.			06/25/2001
	A106	6,593,191	07/15/2003	Fitzgerald			05/16/2001
	A107	6,573,126	06/03/2003	Cheng et al.			08/10/2001
	A108	2002/0096717	07/25/2002	Chu et al.			01/25/2001
	A109	2002/0100942	08/01/2001	Fitzgerald et al.			06/19/2001
	A110	2002/0123167	09/05/2002	Fitzgerald			07/16/2001
	A111	2002/0123183	09/05/2002	Fitzgerald			07/16/2001
	A112	2002/0123197	09/05/2002	Fitzgerald et al.			06/19/2001
	A113	2002/0125471	09/12/2002	Fitzgerald et al.			12/04/2001
	A114	2002/0125497	09/12/2002	Fitzgerald			07/16/2001
	A115	6,603,156	08/05/2003	Rim			03/31/2001
<i>HL</i>	A116	2003/0003679	01/02/2003	Doyle et al.			06/29/2001

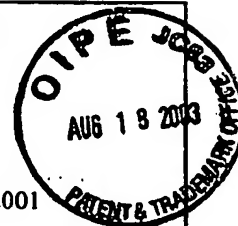
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DATE CONSIDERED

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## FOREIGN PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
<i>Handwritten initials</i>	B1	41 01 167	07/23/1992	DE				NO	NO
	B2	0 587 520	03/16/1994	EP				NO	YES
	B3	0 683 522	11/22/1995	EP				NO	YES
	B4	0 828 296	03/11/1998	EP				NO	YES
	B5	0 829 908	03/18/1998	EP				NO	YES
	B6	0 838 858	04/29/1998	EP				NO	NO
	B7	1 020 900	07/19/2000	EP				NO	YES
	B8	1 174 928	01/23/2002	EP				NO	YES
	B9	2 342 777	04/19/2000	GB				YES	YES
	B10	10-270685	10/09/1998	JP				NO	YES
	B11	11-233744	08/27/1999	JP				NO	NO
	B12	2000-021783	08/31/2000	JP				NO	YES
	B13	2000-031491	01/28/2000	JP				NO	NO
	B14	2001-319935	11/16/2001	JP				NO	YES
	B15	2002-076334	03/15/2002	JP				NO	YES
	B16	2002-164520	06/07/2002	JP				NO	YES
	B17	2002-289533	10/04/2002	JP				NO	YES
	B18	4-307974	10/30/1992	JP				NO	NO
	B19	5-166724	07/02/1993	JP				NO	Abstract Only
	B20	6-177046	06/24/1994	JP				NO	Abstract Only
	B21	7-106446	04/21/1995	JP				NO	NO
	B22	7-240372	09/12/1995	JP				NO	Abstract Only
<i>Handwritten initials</i>	B23	00/48239	08/17/2000	WO				NO	YES
<i>Handwritten initials</i>	B24	00/54338	09/14/2000	WO				NO	YES


<b>EXAMINER</b> <i>Wesley Schultz</i>	<b>DATE CONSIDERED</b> <i>8/4/04</i>
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EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
<i>RL</i>	B25	01/022482	03/29/2001	WO				NO	YES
	B26	01/54202	07/26/2001	WO				NO	YES
	B27	01/93338	12/06/2001	WO				NO	YES
	B28	01/99169	12/27/2001	WO				NO	YES
	B29	02/071488	09/12/2002	WO				NO	YES
	B30	02/071491	09/12/2002	WO				NO	YES
	B31	02/071495	09/12/2002	WO				NO	YES
	B32	02/082514	10/17/2002	WO				NO	YES
	B33	02/13262	02/14/2002	WO				NO	YES
	B34	02/15244	02/21/2002	WO				NO	YES
	B35	02/27783	04/04/2002	WO				NO	YES
	B36	02/47168	06/13/2002	WO				NO	YES
	B37	98/59365	12/30/1998	WO				NO	YES
	B38	99/53539	10/21/1999	WO				NO	YES
<i>RL</i>	B39	6-252046	11/19/1992	JP				NO	YES



EXAMINER <i>Kenneth Schuy</i>	DATE CONSIDERED <i>8/4/04</i>
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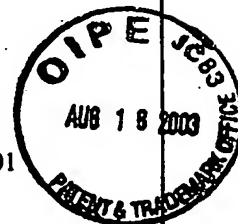


OTHER ART, JOURNAL ARTICLES, ETC.		
EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
<i>[Signature]</i>	C1	Armstrong et al., "Design of Si/SiGe Heterojunction Complementary Metal-Oxide-Semiconductor Transistors," IEDM Technical Digest (1995 International Electron Devices Meeting) pp. 761-764.
	C2	Armstrong, "Technology for SiGe Heterostructure-Based CMOS Devices", PhD Thesis, Massachusetts Institute of Technology, 1999, pp. 1-154.
	C3	Augusto et al., "Proposal for a New Process Flow for the Fabrication of Silicon-based Complementary MOD-MOSFETs without ion Implantation," Thin Solid Films, vol. 294, no. 1-2, pp. 254-258 (February 15, 1997).
	C4	Barradas et al., "RBS analysis of MBE-grown SiGe/(001) Si heterostructures with thin, high Ge content SiGe channels for HMOS transistors," Modern Physics Letters B (2001) (abstract).
	C5	Borenstein et al., "A New Ultra-Hard Etch-Stop Layer for High Precision Micromachining," Proceedings of the 1999 12th IEEE International Conference on Micro Electro Mechanical Systems (MEMS) (January 17-21, 1999) pp. 205-210.
	C6	Bouillon et al., "Search for the optimal channel architecture for 0.18/0.12 $\mu\text{m}$ bulk CMOS Experimental study," IEEE, (1996) pp. 21.2.1-21.2.4.
	C7	Bruehl et al., "SMART CUT: A Promising New SOI Material Technology," Proceedings 1995 IEEE International SOI Conference (October 1995) pp. 178-179.
	C8	Bruehl, "Silicon on Insulator Material Technology," Electronic Letters, Vol. 13, No. 14 (July 6, 1995) pp. 1201-1202.
	C9	Bufler et al., "Hole transport in strained Si <sub>1-x</sub> Ge <sub>x</sub> alloys on Si <sub>1-y</sub> Ge <sub>y</sub> substrates," Journal of Applied Physics, Vol. 84, No. 10 (November 15, 1998) pp. 5597-5602.
	C10	Burghartz et al., "Microwave Inductors and Capacitors in Standard Multilevel Interconnect Silicon Technology", IEEE Transactions on Microwave Theory and Techniques, Vol. 44, No. 1, January 1996, pp. 100-104.
	C11	Canaperi et al., "Preparation of a relaxed Si-Ge layer on an insulator in fabricating high-speed semiconductor devices with strained epitaxial films," International Business Machines Corporation, USA (2002) (abstract).
	C12	Carlin et al., "High Efficiency GaAs-on-Si Solar Cells with High Voc Using Graded GeSi Buffers," IEEE (2000) pp. 1006-1011
	C13	Chang et al., "Selective Etching of SiGe/Si Heterostructures," Journal of the Electrochemical Society, No. 1 (January 1991) pp. 202-204.
	C14	Cheng et al., "Electron Mobility Enhancement in Strained-Si n-MOSFETs Fabricated on SiGe-on-Insulator (SGOI) Substrates," IEEE Electron Device Letters, Vol. 22, No. 7 (July 2001) pp. 321-323.
<i>[Signature]</i>	C15	Cheng et al., "Relaxed Silicon-Germanium on Insulator Substrate by Layer Transfer," Journal of Electronic Materials, Vol. 30, No. 12 (2001) pp. L37-L39.

EXAMINER <i>Heena Singh</i>	DATE CONSIDERED <i>8/4/04</i>
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**OTHER ART, JOURNAL ARTICLES, ETC.**

EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
<i>Kh</i>	C16	Cullis et al., "Growth ripples upon strained SiGe epitaxial layers on Si and misfit dislocation interactions," Journal of Vacuum Science and Technology A, Vol. 12, No. 4 (July/August 1994) pp. 1924-1931.
	C17	Currie et al., "Carrier mobilities and process stability of strained S in- and p-MOSFETs on SiGe virtual substrates," J. Vac. Sci. Technol. B., Vol. 19, No. 6 (Nov/Dec 2001) pp. 2268-2279.
	C18	Eaglesham et al., "Dislocation-Free Stranski-Krastanow Growth of Ge on Si(100)," Physical Review Letters, Vol. 64, No. 16 (April 16, 1990) pp. 1943-1946.
	C19	Feijoo et al., "Epitaxial Si-Ge Etch Stop Layers with Ethylene Diamine Pyrocatechol for Bonded and Etchback Silicon-on-Insulator," Journal of Electronic Materials, Vol. 23, No. 6 (June 1994) pp. 493-496.
	C20	Fischetti et al., "Band structure, deformation potentials, and carrier mobility in strained Si, Ge, and SiGe alloys," J. Appl. Phys., Vol. 80, No. 4 (August 15, 1996) pp. 2234-2252.
	C21	Fischetti, "Long-range Coulomb interactions in small Si devices. Part II. Effective electron mobility in thin-oxide structures," Journal of Applied Physics, Vol. 89, No. 2 (January 15, 2001) pp. 1232-1250.
	C22	Fitzgerald et al., "Dislocation dynamics in relaxed graded composition semiconductors," Materials Science and Engineering B67, (1999) pp. 53-61.
	C23	Fitzgerald et al., "Relaxed GexSi1-x structures for III-V integration with Si and high mobility two-dimensional electron gases in Si," AT&T Bell Laboratories, Murray Hill, NJ 07974 (1992) American Vacuum Society, pp. 1807-1819
	C24	Fitzgerald et al., "Totally Relaxed GexSi1-x Layers with Low Threading Dislocation Densities Grown on Si Substrates," Applied Physics Letters, Vol. 59, No. 7 (August 12, 1991) pp. 811-813.
	C25	Garone et al., "Silicon vapor phase epitaxial growth catalysis by the presence of germane," Applied Physics Letters, Vol. 56, No. 13 (March 26, 1990) pp. 1275-1277.
	C26	Gray and Meyer, "Analysis and Design of Analog Integrated Circuits", John Wiley & Sons, 1984, pp. 605-632.
	C27	Grützmacher et al., "Ge segregation in SiGe/Si heterostructures and its dependence on deposition technique and growth atmosphere," Applied Physics Letters, Vol. 63, No. 18 (November 1, 1993) pp. 2531-2533.
	C28	Hackbarth et al., "Alternatives to thick MBE-grown relaxed SiGe buffers," Thin Solid Films, Vol. 369, No. 1-2 (July 2000) pp. 148-151.
	C29	Hackbarth et al., "Strain relieved SiGe buffers for Si-based heterostructure field-effect transistors," Journal of Crystal Growth, Vol. 201/202 (1999) pp. 734-738.
	C30	Herzog et al., "SiGe-based FETs: buffer issues and device results," Thin Solid Films, Vol. 380 (2000) pp. 36-41.
<i>Kh</i>	C31	Höck et al., "Carrier mobilities in modulation doped Si1-xGex heterostructures with respect to FET applications," Thin Solid Films, Vol. 336 (1998) pp. 141-144.

EXAMINER

*Howard Schuyt*

DATE CONSIDERED

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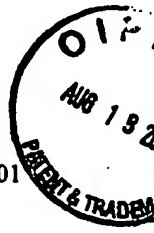
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**OTHER ART, JOURNAL ARTICLES, ETC.**

EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
<i>He</i>	C32	Höck et al., "High hole mobility in Si <sub>0.17</sub> Ge <sub>0.83</sub> channel metal-oxide-semiconductor field-effect transistors grown by plasma-enhanced chemical vapor deposition," Applied Physics Letters, Volume 76, No. 26 (June 26, 2000) pp. 3920-3922.
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	C45	König et al., "Design Rules for n-Type SiGe Hetero FETs," Solid State Electronics, Vol. 41, No. 10 (1997), pp. 1541-1547.
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	C47	König et al., "SiGe HBTs and HFETs," Solid-State Electronics, Vol. 38, No. 9 (1995) pp. 1595-1602.
<i>1</i>	C48	Kuznetsov et al., "Technology for high-performance n-channel SiGe modulation-doped field-effect transistors," J. Vac. Sci. Technol., B 13(6), pp. 2892-2896 (November/December 1995).
<i>He</i>	C49	Larson, "Integrated Circuit Technology Options for RFIC's Present Status and Future Directions", IEEE Journal of Solid-State Circuits, Vol. 33, No. 3, March 1998, pp. 387-399.


<b>EXAMINER</b> <i>Norma Schulz</i>	<b>DATE CONSIDERED</b> <i>8/4/04</i>
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FORM PTO - 1449		ATTY DOCKET NO.: ASC-023DVC2
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT		APPLICANTS: Fitzgerald
		SERIAL NO.: 10/022,689
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		GROUP: 2813



OTHER ART, JOURNAL ARTICLES, ETC.		
EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
<i>JS</i>	C50	Lee and Wong, "CMOS RF Integrated Circuits at 5 GHz and Beyond", Proceedings of the IEEE, Vol. 88, No. 10, October 2000, pp. 1560-1571.
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	C58	M. Kummer et al., "Low energy plasma enhanced chemical vapor deposition," Materials Science and Engineering B89 (2002) pp. 288-295.
	C59	Maiti et al., "Strained-Si heterostructure field effect transistors," Semicond. Sci. Technol., Vol. 13 (1998) pp. 1225-1246.
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	C61	Meyerson et al., "Cooperative Growth Phenomena in Silicon/Germanium Low-Temperature Epitaxy," Applied Physics Letters, Vol. 53, No. 25 (December 19, 1988) pp. 2555-2557.
	C62	Mizuno et al., "Advanced SOI-MOSFETs with Strained-Si Channel for High Speed CMOS-Electron/Hole Mobility Enhancement," 2002 Symposium on VLSI Technology, Digest of Technical Papers, Honolulu, (June 13-15), IEEE New York, NY, pp. 210-211.
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EXAMINER <i>Wanda Schuff</i>	DATE CONSIDERED <i>8/4/04</i>
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## OTHER ART, JOURNAL ARTICLES, ETC.

EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
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	C67	Papananos, "Radio-Frequency Microelectronic Circuits for Telecommunication Applications", Kluwer Academic Publishers, 1999, pp. 115-117, 188-193.
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	C69	Parker et al., "SiGe heterostructure CMOS circuits and applications," Solid State Electronics, Vol. 43 (1999) pp. 1497-1506.
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	C78	Sugimoto and Ueno, "A 2V, 500 MHz and 3V, 920 MHz Low-Power Current-Mode 0.6 $\mu$ m CMOS VCO Circuit", IEICE Trans. Electron., Vol. E82-C, No. 7, July 1999, pp. 1327-1329.
	C79	Ternent et al., "Metal Gate Strained Silicon MOSFETs for Microwave Integrated Circuits", IEEE October 2000, pp. 38-43.
	C80	Tweet et al., "Factors determining the composition of strained GeSi layers grown with disilane and germane," Applied Physics Letters, Vol. 65, No. 20 (November 14, 1994) pp. 2579-2581.
	C81	Usami et al., "Spectroscopic study of Si-based quantum wells with neighboring confinement structure," Semicon. Sci. Technol. (1997) (abstract).
<i>W</i>	C82	Welser et al., "Electron Mobility Enhancement in Strained-Si N-Type Metal-Oxide-Semiconductor Field-Effect Transistors," IEEE Electron Device Letters, Vol. 15, No. 3 (March 1994) pp. 100-102.

EXAMINER <i>Lawrence Schuff</i>	DATE CONSIDERED <i>8/4/04</i>
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OTHER ART, JOURNAL ARTICLES, ETC.		
EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)	
<i>He</i>	C83	Welser, "The Application of Strained Silicon/Relaxed Silicon Germanium Heterostructures to Metal-Oxide-Semiconductor Field-Effect Transistors," PhD Thesis, Stanford University, 1994, pp. 1-205.
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<i>He</i>	C94	Yamagata et al., "Bonding, Splitting and Thinning by Porous Si in ELTRAN®; SOI-Epi Wafer™," Mat. Res. Soc. Symp. Proc., Vol. 681E (2001) pp. 18.2.1-18.2.10.

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EXAMINER	<i>Harina Schuf</i>	DATE CONSIDERED	<i>8/4/04</i>
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